

## PATENT ABSTRACTS OF JAPAN

(11)Publication number : 63-218522

(43)Date of publication of application : 12.09.1988

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(51)Int.Cl.

C03B 32/00  
C03B 20/00

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(21)Application number : 62-049912

(71)Applicant : TOSOH CORP

(22)Date of filing : 06.03.1987

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### (54) METHOD FOR REMOVING STRAIN IN QUARTZ GLASS

#### (57)Abstract:

PURPOSE: To remove strain in quartz glass without generating crystallization and almost keeping the previous shape before removing strain, by heating a quartz glass contg. strain at a temp. above a specified temp. in an inert-gaseous atmosphere.

CONSTITUTION: The strain in the quartz glass is removed by heating the quartz glass contg. strain at  $\geq 1,200^{\circ}\text{C}$  in the inert gaseous atmosphere. A gas selected among rare gases and gaseous nitrogen, or a gaseous mixture of the above- mentioned gases is favorable as the inert gas. When the glass is heated at  $\geq 1,500^{\circ}\text{C}$  order, the shape of the glass extremely changes because said glass is fluidized at that temp. A powder which is inert to the quartz glass is favorable to be packed around the quartz glass in order to prevent the change of shape. Powder of  $\text{SiO}_2$ , C, SiC, stabilized  $\text{ZrO}_2$  are exemplified as the powder to be packed.

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### LEGAL STATUS

[Date of request for examination]

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's  
decision of rejection]

[Date of requesting appeal against examiner's  
decision of rejection]

[Date of extinction of right]

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